

ABSTRACT

Disclosed is a method of manufacturing a thin film magnetic head, which enables a magnetic pole portion to be formed with high precision in a short time. After forming a mask precursor pattern by patterning an alumina layer, the mask precursor pattern is subjected to an etching process of ion milling, thereby forming a first mask. The width of a portion in the first mask is narrower than the width of the minimum pattern which can be formed by a photolithography process. Consequently, by performing the etching process, the width of the portion of the first mask can be narrowed.

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